Customer No.: 31561 Application No.: 10/711,533 Docket No.: 13791-US-PA

## REMARKS

## Present Status of the Application

In the Office Action, claims 1-7 were rejected under 35 U.S.C. 102(b) as being anticipated by Kasai et al. (U.S. Patent NO. 6,190,987). In addition, claims 8-25 are allowed. The reason for allowance is that it is not obvious to one of ordinary skill in the art to put down a metal silicide on the doped region on the opening of the conductive layer. Applicants would like to thank the Examiner for the allowance of claims 8-25. Reconsideration and allowance of claims 1-7 is respectfully requested.

## Discussion of Office Action Rejections

The Office Action rejected claims 1-7 under 35 U.S.C. 102(b) as being anticipated by Kasai et al. (U.S. Patent NO. 6,190,987). Applicants have amended claim 1 and added claim 26 to more explicitly describe the claimed invention. It is believed that no new matter adds by way of amendment to claims or otherwise to the application.

Independent claim 1 recites the features as follows:

1. A method of fabricating a capacitor, comprising: forming a dielectric layer on a semiconductor substrate;

forming an upper electrode on the dielectric layer, the upper electrode having a plurality of opening therein;

performing a doping step to the semiconductor substrate through the openings to form a single doped region as a lower electrode in the semiconductor substrate under the upper electrode; and

forming a plurality of metal silicide layers on portions of the single doped region within the openings.

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(emphasis added).

Claims 2-7 and 26 also recite the similar features.

In re U.S. Patent NO. 6,190,987, Kasai et al. fail to disclose that a plurality of metal silicide layers are formed on portions of the single doped region within the openings. Therefore, claim 1 is patentable over prior art (U.S. Patent NO. 6,190,987) and is in proper condition for allowance. If independent claim 1 is allowable over the prior art of record, then its dependent claims 2-7 and 26 are allowable as a matter of law, because these dependent claims contain all features of their respective independent claim 1. In re Fine, 837 F.2d 1071 (Fed. Cir. 1988).

For at least the foregoing reasons, Applicant respectfully submits that claims 1-7 and 26 are in proper condition for allowance. Reconsideration is respectfully requested.

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## **CONCLUSION**

For at least the foregoing reasons, it is believed that all pending claims 1-26 are in proper condition for allowance. If the Examiner believes that a conference would be of value in expediting the prosecution of this application, he is cordially invited to telephone the undersigned counsel to arrange for such a conference.

Date: Harel 3, 2006

Respectfully submitted,

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